

Supplementary

Lithography-Free Route to Hierarchical Structuring of High- χ Block Copolymers on a Gradient Patterned Surface

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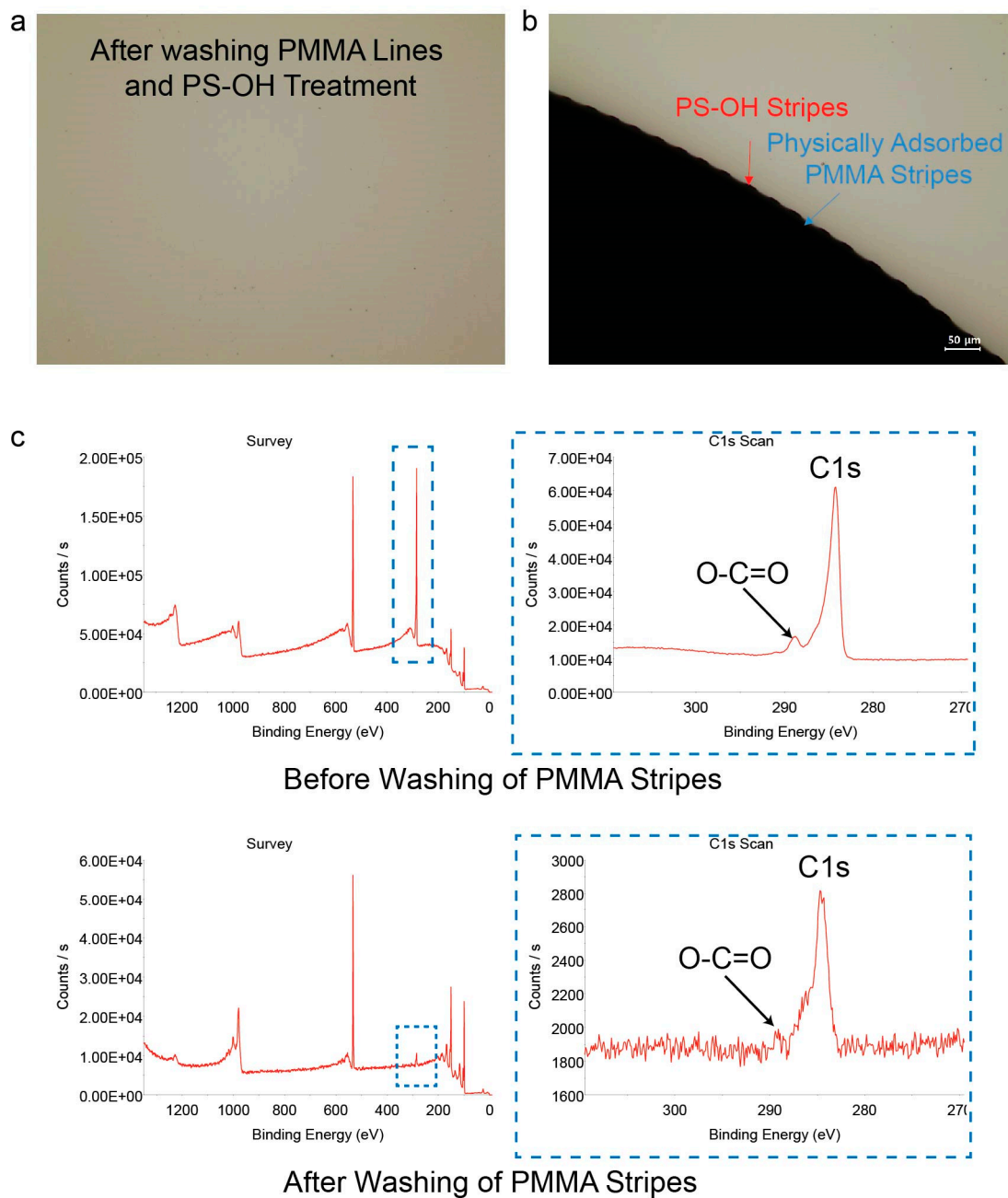


Figure S1. OM observation and XPS investigation of PMMA adsorption on to SiO_x surface.

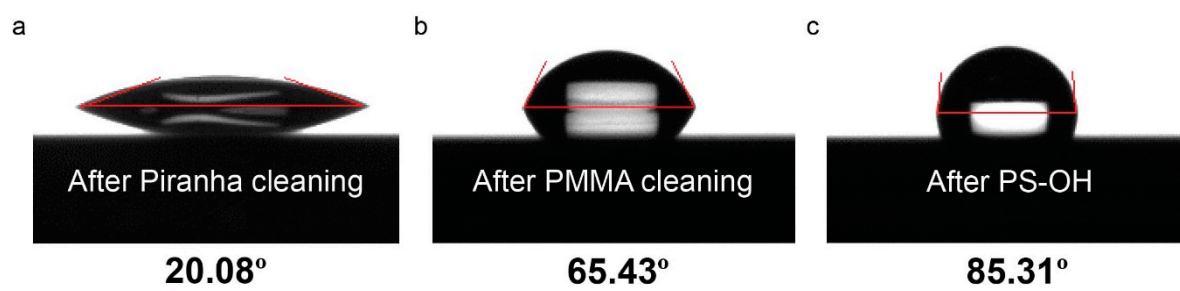


Figure S2: Contact angle measurements of different surfaces.